## **AMENDMENTS TO THE CLAIMS**

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Please amend the claims as follows:

1.(currently amended) A pedestal supporting a substrate in a plasma chamber, comprising: an insulating base <u>comprising a recess</u>;

a conductive layer comprising a bottom portion with a bottom width accommodated in the recess and an upper portion with an upper width not accommodated in the recess-on-the insulating base; and

a ceramic cover at least partially covering the conductive layer, the conductive layer being covered when the pedestal supports a substrate.

2. (currently amended) The pedestal in claim 1, wherein the conductive layer further comprises a bottom portion with a bottom width and an upper portion with an upper width, the upper width being is less than the bottom width and a diameter of the substrate.

## 3. (cancelled)

- 4. (original) The pedestal in claim 1, wherein the ceramic cover further overlies the insulating base.
- 5. (original) The pedestal in claim 1, wherein the ceramic cover further comprises an opening exposing the conductive layer.
- 6. (currently amended) The pedestal in claim 21, wherein the ceramic cover overlies the bottom portion of the conductive layer and further comprises a hollow portion accommodating the upper portion of the conductive layer.
- 7. (original) The pedestal in claim 1, wherein the ceramic cover is ring-shaped.
- 8. (original) The pedestal in claim 1, wherein the insulating base comprises silicon oxide.

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9. (original) The pedestal in claim 1, wherein the conductive layer comprises titanium.

10. (original) The pedestal in claim 1, wherein the ceramic cover comprises aluminum oxide.

11. (currently amended) A pedestal supporting a substrate in a plasma chamber, comprising:

an insulating base having a recess;

a conductive layer embedded in the recess; and

a ceramic cover overlying the insulating base and partially covering the conductive layer;

wherein

the conductive layer is covered when the pedestal supports a substrate and the conductive layer further comprises an upper portion protruding from the recess.

12. (currently amended) The pedestal in claim 11, wherein the conductive layer further comprises an the upper portion, is with a width less than the diameter of the substrate, protruding from the recess.

13. (currently amended) The pedestal in claim 11, wherein the conductive layer further comprises an upper portion, with a width of the upper portion is less than the diameter of the substrate and the width of the other portion of the conductive layer, protruding from the recess.

14. (original) The pedestal in claim 13, wherein the ceramic cover further comprises a hollow portion accommodating the upper portion of the conductive layer.

15. (original) The pedestal in claim 13, wherein the ceramic cover further comprises a hollow portion accommodating the upper portion of the conductive layer and exposing the narrower upper portion of the conductive layer.

16. (original) The pedestal in claim 11, wherein the ceramic cover is ring-shaped.

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17. (original) The pedestal in claim 11, wherein the insulating base comprises silicon oxide.

18. (original) The pedestal in claim 11, wherein the conductive layer comprises titanium.

19. (original) The pedestal in claim 11, wherein the ceramic cover comprises aluminum oxide.

20. (currently amended) A pedestal supporting a substrate in a plasma chamber, comprising:

a silicon-oxide base having a recess;

a titanium layer having a bottom portion embedded in the recess, and an upper portion,

narrower than the bottom portion and the substrate, protruding from the recess; and

a ring-shaped ceramic cover, having a hollow portion accommodating the upper portion

of the titanium layer therein, overlying the insulating silicon-oxide base and a portion of the

bottom portion of the titanium layer;

wherein the conductive layer is covered when the pedestal supports the substrate.

21. (currently amended) The method pedestal as claimed in claim 20, wherein the hollow portion

of the ceramic cover further exposes the upper portion of the titanium layer.

22. (original) The pedestal in claim 20, wherein the ceramic cover comprises aluminum oxide.

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